



## Gas sensing properties of thermally evaporated lamellar MoO<sub>3</sub>

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### ABSTRACT

In this work, MoO<sub>3</sub> was thermally evaporated onto gold interdigital fingers on quartz substrates and characterized using X-ray diffraction (XRD), scanning electron microscopy (SEM), and transmission electron microscopy (TEM) techniques. The deposited MoO<sub>3</sub> consist of stratified long rectangles (average length of 50 μm width of 5 μm and thickness of 500 nm) which are predominantly orthorhombic (α-MoO<sub>3</sub>). Each of these plates was composed of many nano-thick layers (average ~30 nm) placed by Van der Waals forces on top of each other forming lamellar patterns. The devices were used as sensors and exhibited considerable change in surface conductivity when exposed to NO<sub>2</sub> and H<sub>2</sub> gases at elevated temperature of 225 °C. The structural and gas sensing properties of thermally evaporated MoO<sub>3</sub> thin films were investigated.

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### 1. Introduction

Semiconductor metal oxide thin films have been extensively used for gas sensors as their conductivity changes due to interactions with gas molecules [1,2]. Such sensors also offer low cost, easy fabrication and consistent performance with respect to other type of gas sensors. Recently, there is an increasing trend to use specifically engineered structured materials as gas sensing elements [2–5]. The use of such structured materials such as belts, rods and wires in micro-, meso- or nano-dimensions, offer high surface to volume ratios and unique structural features that are expected to enhance the properties and performance of gas sensors [6–8]. Such structured oxide based chemical sensors were also found to decrease the device response time due to rapid diffusion of gaseous species into the materials' micro-, meso- and nano-porosities [5,6].

Among the semiconductor metal oxides, MoO<sub>3</sub> with a band gap energy of 2.39–2.9 eV is an excellent candidate for catalytic, electrochromic and gas sensing applications [9,10]. MoO<sub>3</sub> has been well known for its application as a catalyst for the oxidation of hydrocarbons and reduction of NO<sub>x</sub> in the chemical and petroleum industry [11–14]. Efforts were also made to examine and improve the gas sensing properties of MoO<sub>3</sub> based devices to detect H<sub>2</sub> [10,15], CO [15,16], NH<sub>3</sub> [10,12,17], and LPG [10]. Imawan et al. [17] studied the

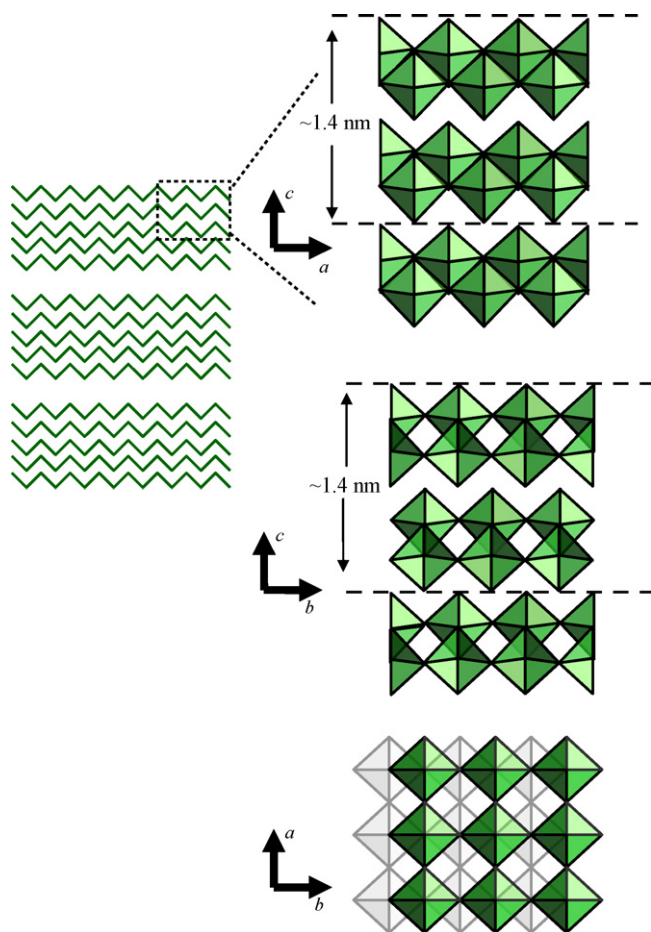
RF sputtered MoO<sub>3</sub> thin films for sensing responses to various gases, including CO, CH<sub>4</sub>, SO<sub>2</sub>, NO<sub>2</sub> and NH<sub>3</sub> in the temperature range of 250 °C and 475 °C. They revealed that MoO<sub>3</sub> was highly sensitive to NH<sub>3</sub> at 425 °C and that the gas sensitivity dropped with decreasing film thickness (<300 nm). Multilayered sputter deposited MoO<sub>3</sub> by the same research group resulted in improved H<sub>2</sub> sensing properties and low cross sensitivity towards NH<sub>3</sub> [15]. It is also shown that the sensitivity and selectivity to target gases can be altered by adding other metal oxides to MoO<sub>3</sub> [1,18,19].

A number of techniques was reported for the deposition of MoO<sub>3</sub> including pulse laser deposition [12], thermal evaporation [20], sputtering [21], sol-gel [1,22], spray pyrolysis [23], chemical vapour deposition [24,25], and electro-deposition [26]. The deposition of MoO<sub>3</sub> using evaporative techniques is advantageous as it can produce highly crystalline and stratified structures. This is an important feature since high crystallinity and having layered formation can allow for greater sensitivity. MoO<sub>3</sub> can obtain an orthorhombic structure with double layers of linked MoO<sub>6</sub> octahedra (Fig. 1), parallel to [0 1 0] direction [10]. Each of these double layers consists of zig-zag chains along [0 0 1] of octahedra sharing edges. The double layers are held together by Van der Waals forces to make stratified structures [10,27].

The electrical conductance of a semiconducting oxide-based gas sensor depends on the chemisorbed oxygen ions, oxygen vacancies and the interstitial ions. The target gases change the oxygen balance of the oxide sensor, leading to a variation in its conductance. It is believed that in most of semiconducting oxide-based devices, the

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**Fig. 1.** Representations of  $\alpha$ - $\text{MoO}_3$ : the formation of secondary crystallite network (left) of edge- and corner-sharing  $\text{MoO}_6$  octahedra viewed along different crystallographic planes (right). The secondary network (25 nm in our case) forms the tertiary thicker layers.

chemisorbed oxygen is involved in their sensing action at elevated temperatures [6,28,29].

In the case of a  $\text{MoO}_3$  sensitive layer, direct adsorption has been proposed for oxidizing gases such as  $\text{NO}_2$  and  $\text{O}_2$  [7]. In such cases, oxidizing gases reduce oxygen defects [30]. Reducing gases such as  $\text{H}_2$ , typically react with adsorbed oxygen from the environment. Comini et al. [2] have studied gas sensing properties of  $\text{MoO}_3$  nanorods deposited on alumina substrates toward CO and  $\text{CH}_3\text{OH}$  by varying the gas concentration between 10 and 1000 ppm at 40% relative humidity (RH) and at the working temperature of 200 °C. In the case of CO, they have utilized the common mechanism for oxide thin films to explain the gas sensing properties. According to this explanation, when CO is fed into the test chamber, the conductance of the  $\text{MoO}_3$  layer increases, due to the exchange of electrons between the ionosorbed species and the semiconductor itself. CO reacts with oxygen species adsorbed on the semiconductor ( $\text{O}^{2-}$ ,  $\text{O}^-$ ,  $\text{O}_2^-$ ) with a consequent increase in the conductance. However, a more accurate explanation has been presented by Choi and Thompson [31] who have studied changes in the  $\text{MoO}_3$  surface using XPS in response to  $\text{H}_2$ . They observed that at 400 °C, the surface concentration of  $\text{Mo}^{6+}$  decreased and changed to lower oxidation states of  $\text{Mo}^{5+}$  and  $\text{Mo}^{4+}$ . This result indicates that the surface of  $\text{MoO}_3$  is the most sensitive part of the crystal to be reduced by hydrogen. When oxygen is removed, orthorhombic  $\text{MoO}_3$  is capable of forming shear structures, which facilitates the rearrangement of the polyhedra links: a change from corner-sharing octahedral either to edge-sharing or face-sharing octahedra. For  $\text{MoO}_6$  octa-

hedra, energy of the edge-linked system is considerably lower than the corner-linked system making the reaction highly favourable [10,32]. As a result, when  $\text{MoO}_3$  is exposed to a reducing target gas, the involvement of its lattice oxygen can cause the change of conductivity. Reaction of  $\text{MoO}_3$  at elevated temperatures has also been studied by different researchers [33,34] and it has been confirmed that in the range of 350–400 °C, the reaction on the surface of  $\text{MoO}_3$  can lead to the appearance of surface domains forming crystallographic shear planes.

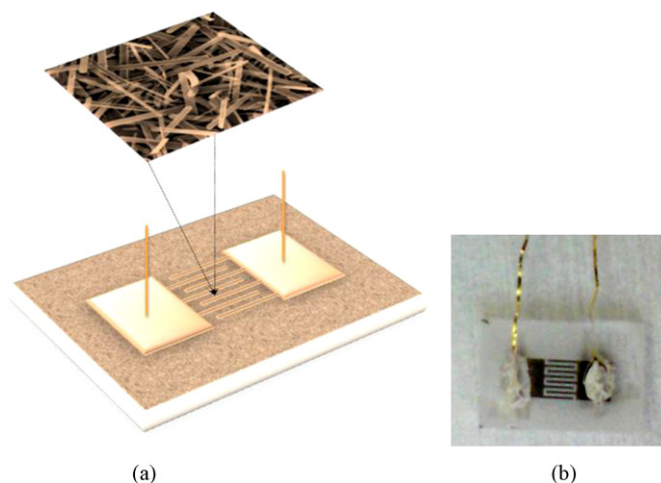
In this paper, the authors report about the response of  $\text{MoO}_3$  thin films to low concentrations of  $\text{NO}_2$  and  $\text{H}_2$ . It emerges that the film exhibit good response to these gases at the temperature range of 200–300 °C. In this work, thermal evaporation technique has been used for the deposition of  $\text{MoO}_3$ . Samples were characterized using X-ray diffraction (XRD), scanning electron microscopy (SEM), and transmission electron microscopy (TEM) techniques.

## 2. Experimental

Fresh quartz substrates were cleaned with acetone, isopropanol and DI water and consequently cut into 8 mm × 12 mm pieces for the deposition of  $\text{MoO}_3$ . An interdigital finger pattern of 100 nm thickness (gold/titanium) was deposited by sputtering and patterned by photolithography as the electrodes for conductometric sensing (Fig. 2).

$\text{MoO}_3$  powder (China Rare Metal Material Co.) was weighed at 10 mg and placed at the centre of a furnace at the temperature of 770 °C. The substrates were placed at a distance of 12 cm from the hot spot at a temperature of approximately 450 °C and thermal deposition was carried out using a carrier gas of 10% oxygen balanced in argon. Oxygen gas was added to the system to improve the stoichiometric formation of fully oxidized  $\text{MoO}_3$ . Deposition was carried out for a duration of 30 min and the evaporation temperature was increased slowly at the rate of 2 °C per min and cooled at the same rate after the procedure. A constant gas flow of approximately 800 sccm was utilized.

The SEM characterization was carried out using a FEI Nova NanoSEM. The TEM characterization was carried out using a JEOL JEM 1010 electron microscope. Samples for TEM were prepared by scratching the sample in ethanol, and subsequently drop casting the samples onto a Cu TEM grid. The XRD analysis was carried out using a Bruker D8 Discover microdiffractometer fitted with a GADDS (General Area Detector Diffraction System). Data was collected at room temperature using  $\text{CuK}\alpha$  radiation ( $\lambda = 1.54178 \text{ \AA}$ ) with a potential of 40 kV and a current of 40 mA, and filtered with a



**Fig. 2.** (a) Schematic view and (b) picture of conductometric  $\text{MoO}_3$  based sensor.

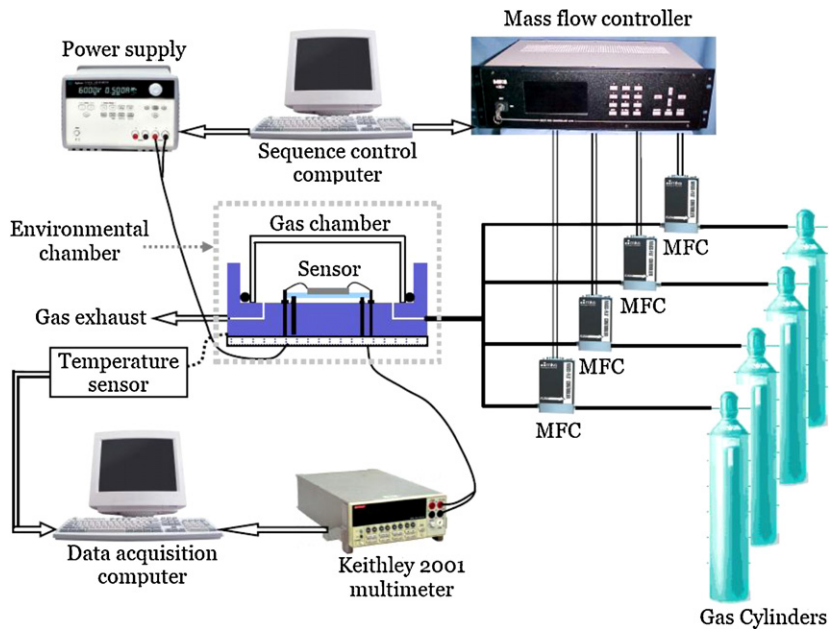


Fig. 3. Schematic view of multi-channel gas sensing measurement system.

graphite monochromator in the parallel mode (175 mm collimator with 0.5 mm pinholes).

MoO<sub>3</sub> conductometric sensors were mounted on an electric heater. Gas response measurements of the devices were performed in a test chamber made from Teflon, which was sealed in a quartz lid. The heater was controlled by a regulated DC power supply providing different operating temperatures. The output resistance as a function of time across the conductometric sensor during gas exposure was measured using a multimeter (Keithley 2001). A computerized gas calibration system, with mass flow controllers, was used for exposing the sensor to different concentrations of NO<sub>2</sub> and H<sub>2</sub> gases (Fig. 3). The total flow rate was kept constant at 200 sccm and dry synthetic air was used as the reference gas. At each operating temperature, the baseline gas was maintained for a duration of 120 min to allow the device to stabilize. Subsequently, the device was exposed to sequences of different concentrations of NO<sub>2</sub> and H<sub>2</sub> for several hours. The sensor temperature was varied in the 20–300 °C range. Each NO<sub>2</sub> gas sequence consisted of 0.6, 1.25, 2.5, 5 and 10 ppm balanced in synthetic air. A second pulse of 1.25 ppm was utilized to confirm its repeatability. Concentration of H<sub>2</sub> var-

ied in the range of 0.06–1% balanced in synthetic air at constant gas flow of 200 sccm.

### 3. Results and discussion

#### 3.1. Micro-characterization results

It is well known that gas sensing properties of a metal oxide thin film strongly depends on its morphological features. A high surface area facilitates the physisorption and chemisorption processes by increasing the absorption rates [1]. Fig. 4 shows the SEM morphological characterization of the as-deposited MoO<sub>3</sub> prepared by the thermal evaporation method. As can be seen, the MoO<sub>3</sub> thin film is composed of large rectangular plates with the average width and length of 5 and 50 μm, respectively. The inset in the Fig. 4(a) shows the typical thickness of the rectangles which is less than 1 μm (on average 500 nm for the previously described deposition condition), also it shows the layered nature of the rectangles. Fig. 4(b) clarifies that each of these plates were composed of many nano-thick layers with the average thickness of ~30 nm which form the main build-

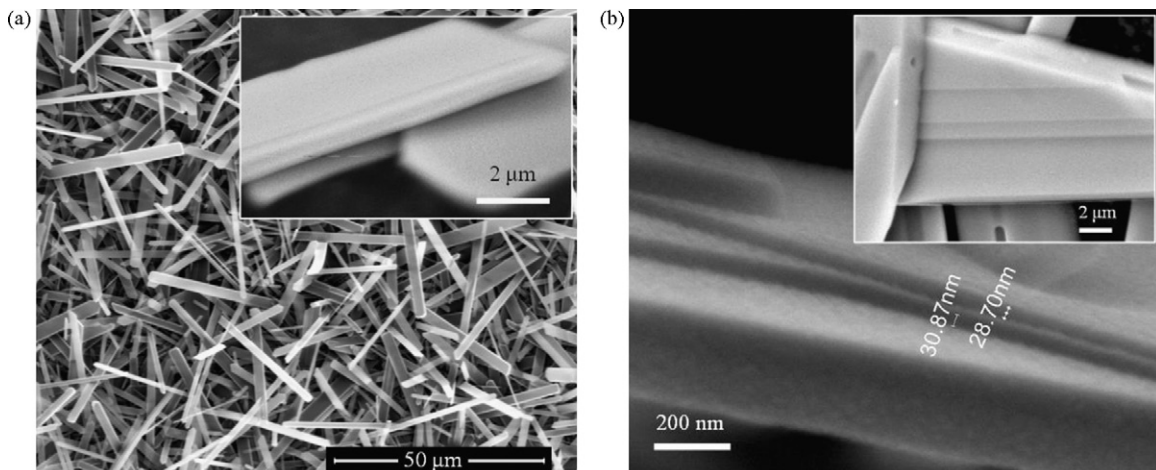


Fig. 4. (a and b) SEM micrographs of as-deposited MoO<sub>3</sub> structures, inset in (a) shows cross sectional SEM (45° rotation) of MoO<sub>3</sub> thin film.

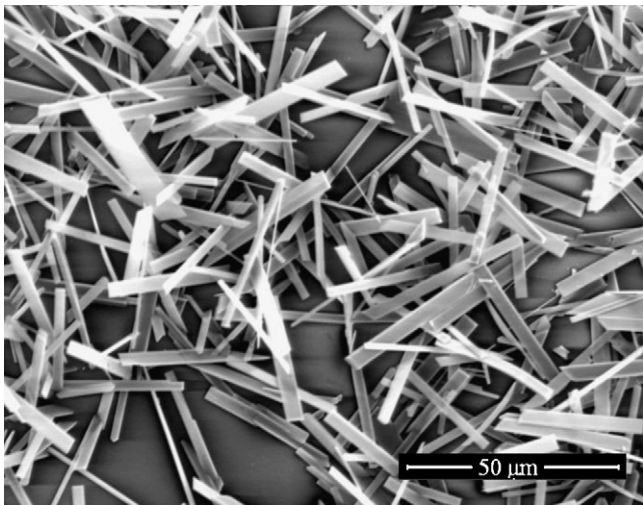


Fig. 5. SEM micrograph of MoO<sub>3</sub> sensor after a long term testing at 300 °C.

ing blocks. It is suggested that such plates are placed by Van der Waals forces on top of each other forming lamellar patterns [10,27]. Mechanical exfoliation (similar to the exfoliation of graphene layers [35]) shows that our α-MoO<sub>3</sub> is made of secondary ~30 nm layers. Stacking of the fundamental double layers of α-MoO<sub>3</sub>, which are 1.4 nm thick each (Fig. 1), forms these secondary layers. Thicker pieces (several hundreds of nm) are made of the secondary layers (SEM of an exfoliated layer is also shown in the SEM of the Siciliano et al.'s 2009 paper [36]).

Fig. 5 shows the surface of the MoO<sub>3</sub> sensor after a long term testing at temperatures as high as 300 °C. As can be observed the concentration of rectangles was decreased. The reason for the change can be attributed to the sublimation of MoO<sub>3</sub> from the sensor's surface due its low sublimation point. MoO<sub>3</sub> shows significant sublimations at temperatures above 700 °C [1].

Fig. 6 shows the XRD pattern of the MoO<sub>3</sub> deposited by thermal evaporation. The peaks were indexed to orthorhombic (α-MoO<sub>3</sub>) crystal structure with lattice parameters of  $a = 3.962 \text{ \AA}$ ,  $b = 13.858 \text{ \AA}$ ,  $c = 3.697 \text{ \AA}$  (JCPDS Card No. 005-0508). The strong diffraction peaks of MoO<sub>3</sub> appear at 12.80, 25.70, 39.00, 58.90 and 67.40° 2θ, which correspond to the (0 2 0), (0 4 0), (0 6 0), (0 8 1) and (0 1 0 0) planes,

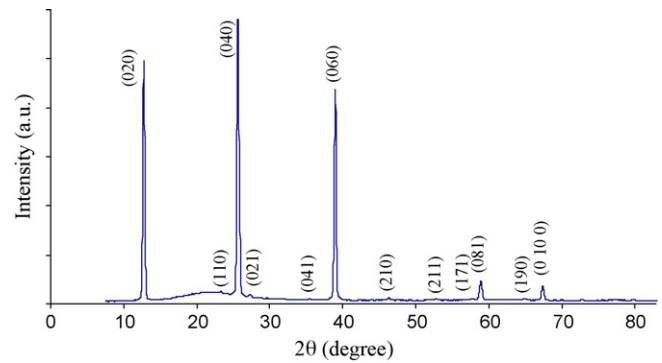


Fig. 6. XRD pattern of MoO<sub>3</sub> deposited by thermal evaporation.

respectively. This reveals that α-MoO<sub>3</sub> long rectangles grow with a strong preferred orientation. The respective peaks have been compared to literature indicating the existence of orthorhombic MoO<sub>3</sub> structures and an α phase. The strong intensity of the reflection peaks of (0 *k* 0) with  $k = 2, 4$  and 6 proves the existence of the lamellar structure [37].

The average crystallite size of the film, which in this case is the thickness of the fundamental secondary layers, can be assessed using the Scherrer's formula [23,36]:

$$G_{hkl} = \frac{0.9\lambda}{\beta \cos \theta} \quad (1)$$

where  $G_{hkl}$  is the average linear dimension of the crystal perpendicular to the diffracting plane ( $hkl$ ),  $\lambda = 1.5406 \text{ \AA}$  is the wavelength of the X-ray radiation used and  $\beta$  is the angular full width of the diffraction peak at the half maximum (FWHM) for the diffraction angle  $2\theta$ . From the XRD spectrum, the assessed thickness of the fundamental secondary layers is approximately 25 nm. As a result, the secondary layers are made of the stacking of about 20–25 of the 1.4 nm fundamental double layers of α-MoO<sub>3</sub> (hence thickness of 25–30 nm). The tertiary large layers (up to several hundreds of nm) are formed from the stacking of these secondary layers. This is also confirmed by the SEM images. Such an observation was also reported by Siciliano et al. [36]. However, they suggested that their main building blocks had the thickness of 85 nm, possibly due to their different deposition conditions.

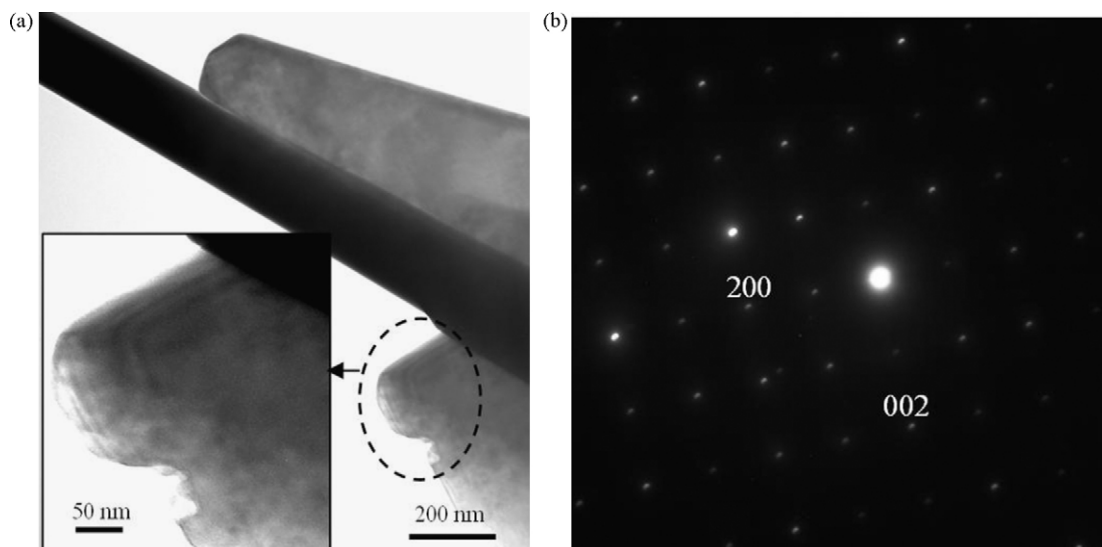


Fig. 7. (a) TEM image of MoO<sub>3</sub> long rectangles and (b) SAED pattern recorded from a thin area.

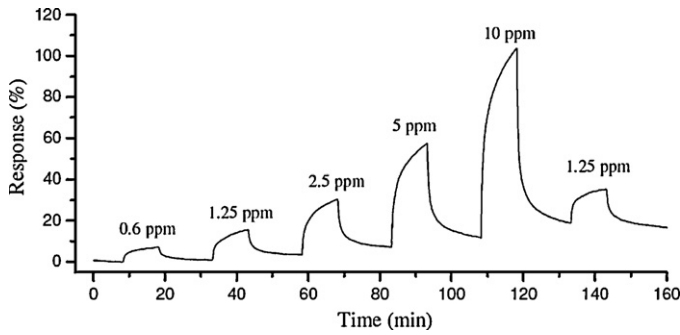


Fig. 8. Dynamic response of the MoO<sub>3</sub> sensor towards different concentrations of NO<sub>2</sub> gas at 225 °C.

Further characterization of the MoO<sub>3</sub> sensitive film was performed using TEM. A typical TEM image of the MoO<sub>3</sub> long rectangles is depicted in Fig. 7(a) with the corresponding surface area electron diffraction pattern (SAED) recorded on the thin area (Fig. 7b). The SAED pattern recorded perpendicular to the growth direction of the structure. It can be attributed to the [0 1 0] zone axis diffraction of orthorhombic MoO<sub>3</sub>. Combined with the TEM information, the SAED study suggests that the long rectangles grow along the [0 0 1] direction, which is consistent with the XRD results [36,37].

### 3.2. Gas sensing results

The developed sensor was tested in a high temperature environment for a range between 180 and 300 °C. At the operating temperature below 180 °C, the resistance of the films was too high to measure (>1 GΩ). Additionally at very high temperatures (above 300 °C), the sensor's baseline was highly unstable and the resistance of the sample increased sharply which could be attributed to the sublimation of MoO<sub>3</sub> and deterioration of the long rectangles (Fig. 5). This observation has also been confirmed by other groups [1,29]. The optimum operating temperature for the sensor response towards H<sub>2</sub> and NO<sub>2</sub> was found to be 225 °C and the results are presented here. Figs. 8 and 9 show dynamic responses of the MoO<sub>3</sub> sensor towards different concentrations of NO<sub>2</sub> and H<sub>2</sub> at 225 °C, respectively. Upon the exposure to NO<sub>2</sub>, the conductivity was decreased and when the sensor was exposed to H<sub>2</sub> gas it increased. The response factor of the sensor in percentage was defined as  $S = (R_{\text{gas}} - R_{\text{air}}) \times 100 / R_{\text{air}}$ , where  $R_{\text{gas}}$  and  $R_{\text{air}}$  denote the resistance of the sensor in the presence of gas and air, respectively.

As discussed in the introduction, surface concentration of H<sub>2</sub> with MoO<sub>3</sub> surface transforms M<sup>6+</sup> to lower oxidation states of Mo<sup>5+</sup> and Mo<sup>4+</sup>. In the temperature range between 100 and 500 °C oxygen chemisorbs over metal oxide, for example, in a molecular (O<sub>2</sub><sup>-</sup>) and atomic form (O<sup>-</sup>). Since O<sub>2</sub><sup>-</sup> has a lower activation energy it is dominating at temperatures below 200 °C and at higher temperature the O<sup>-</sup> form dominates [7]. In the MoO<sub>3</sub> sensor, change

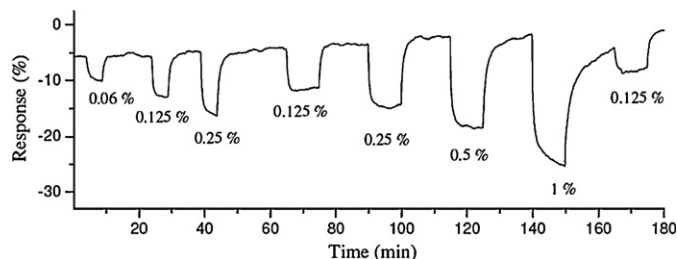


Fig. 9. Dynamic response of the MoO<sub>3</sub> sensor towards different concentrations of H<sub>2</sub> gas at 225 °C.

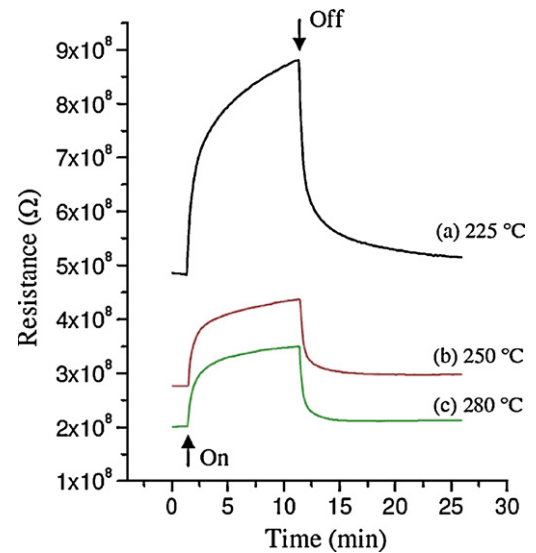


Fig. 10. Dynamic response of the MoO<sub>3</sub> sensor towards 10 ppm NO<sub>2</sub> gas at different temperatures.

in the oxygen balance of the oxide layer leads to a variation in its conductance. For H<sub>2</sub> gas the following interaction may take place:



where H<sub>2(gas)</sub>, H<sub>2(ads)</sub> and O<sup>-</sup><sub>(surface)</sub> represent the H<sub>2</sub> in gas phase, chemisorbed H<sub>2</sub> and surface oxygen ions, respectively. This overall effect releases electrons on the surface and increases the sensor's conductance. In the case of an oxidizing gas (NO<sub>2</sub>), reactions directly take place on the oxide surface. During the interaction process, molecules consume conduction electrons and subsequently increase the depletion region at the surface, and the resistivity of the sensor increases as presented below [3]:



The MoO<sub>3</sub> thin films exhibited a high response to NO<sub>2</sub> and also a considerable response to H<sub>2</sub>. Maximum response was measured to be 118% for 10 ppm NO<sub>2</sub> and 24% for 1% of H<sub>2</sub> at 225 °C. It was also found that the MoO<sub>3</sub> based sensor produce repeatable responses of the same magnitude for both of the gases. Fig. 10 shows the dynamic response characteristics of the MoO<sub>3</sub> sensor towards 10 ppm of NO<sub>2</sub> gas at three different temperatures. As can be seen with increasing the operating temperature the response and the recovery times of the sensor increased, but the response decreased. Therefore, the trade-off between different parameters is needed in choosing the optimum operating temperature. Considering the previously reported works [11,15], our thermally evaporated porous MoO<sub>3</sub> produces larger responses towards NO<sub>2</sub> in comparison with sputtered films.

In order to improve the sensing parameters such as sensitivity, response and recovery time, selectivity and stability, further work should be carried out. It is suggested that the application of different catalysts should also be investigated.

### 4. Conclusion

Thermally evaporated MoO<sub>3</sub> based conductometric gas sensors were developed and their responses towards NO<sub>2</sub> and H<sub>2</sub> were investigated. The MoO<sub>3</sub> thin films consisted of high aspect ratio long rectangles with average length of 50 μm, width of 5 μm

and thickness of 500 nm. Each long rectangle is composed of several nanobelts on top of each other producing a lamellar pattern. The XRD analysis revealed that the MoO<sub>3</sub> thin films are predominantly orthorhombic ( $\alpha$ -MoO<sub>3</sub>) crystal structure. The sensors were tested in a range of temperature between 180 and 300 °C and the study shows that the optimum operating temperature was 225 °C. Maximum response was measured to be 118% for 10 ppm NO<sub>2</sub> and 24% for 1% of H<sub>2</sub> at 225 °C. The results demonstrate that the developed sensors are worthy for further study and commercialization.

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